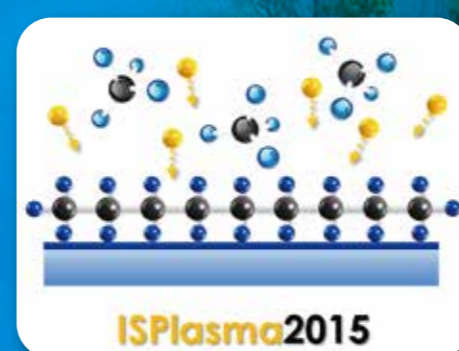


7th International Symposium on Advanced Plasma Science  
and its Applications for Nitrides and Nanomaterials /  
8th International Conference on Plasma-Nano Technology & Science



# ISPlasma2015 IC-PLANTS2015



March 26-31, 2015  
Nagoya University, Japan  
<http://www.isplasma.jp/>

**Chairperson :** Nagahiro Saito, Nagoya University

**Vice-Chairperson :** Keiji Nakamura, Chubu University

Akihiro Wakahara, Toyohashi University of Technology

Noritsugu Umehara, Nagoya University

**Sponsored by :**

The Japan Society of Applied Physics, ISPlasma2015 / IC-PLANTS2015 Organizing Committee

**Co-sponsored by :**

Nagoya University, Nagoya Institute of Technology, Meijo University, Chubu University, Aichi Science & Technology Foundation,  
The Japan Society of Plasma Science and Nuclear Fusion Research, The Japanese Association for Crystal Growth

## Related Fields

**Plasma Science** • Plasma Source • Modeling and Simulation • Thin Film Deposition Process • Etching Process • Atmospheric-pressure plasma • Solution Plasma  
• Advanced Plasma Measuring Technology • Plasma for Clean Energy • Plasma Biology and Medicine • Plasma for Nanotechnology

**Functional Semiconductors** • Crystal Growth of GaN and Related Materials • SiC/Diamond • Optical Devices • MBE Growth of Nitrides • Power device • Electron Devices

**Nanomaterials and Micro fabrication** • Nano structured material • Catalyst/Battery • Solar Cell • Environmental materials • Micro-TAS

**Surface Functionalization** • Hard coating • Thin Films by chemical process • Biosurface and biointerface • Functional thin films

## Special Issue

Selected papers will be published in a special issue of Jpn. J. Appl. Phys. (JJAP). Submission Deadline : April, 2015

## Special Speaker



**Nobel Laureate in Physics**

**Prof. Hiroshi AMANO**

Nagoya University

**March 29, 2015**

**14:00 - 15:20**

Toyoda Auditorium, Nagoya University



## Plenary Speakers

Prof. Yasuhiko ARAKAWA (The University of Tokyo, Japan)

Prof. Vincent M. DONNELLY (University of Houston, USA)

Prof. Hiroyuki MATSUNAMI (Kyoto University, Japan)

Prof. Ravi SILVA (University of Surrey, United Kingdom)

Prof. Kazunari DOMEN (The University of Tokyo, Japan)

Prof. Ulf HELMERSSON (Linkoping University, Sweden)

Prof. Masaharu SHIRATANI (Kyushu University, Japan)

Dr. Koji SUMITOMO (NTT Basic Research Laboratories, Japan)

## Sessions

### Plasma Science

- A1 Plasma Engineering
- A2 Plasma Deposition
- A3 Plasma Medicine
- A4 Plasma Applications
- A5 Atmospheric Pressure Plasma
- A6 Solution Plasma

### Functional Semiconductors

- B1 Nitride Process
- B2 Application of Nitride Semiconductors
- B3 SiC • Diamond • Other Related Materials

### Nanomaterials and Nano/Micro Fabrication

- C1 Nanostructured and Nanocomposite Materials
- C2 Catalyst / Battery
- C3 Solar Cell
- C4 Environmental and Energy Materials
- C5 Microfluidics, Nanofluidics, and microTAS

### Surface Functionalization

- D1 Hard Coating
- D2 Wet Coating
- D3 Functional Thin Films
- D4 Biosurface

**Registration** Advanced Online Registration is required.

**General Student**

Registration Fee: Early Registration — JPY 45,000 JPY 15,000  
(Before Feb 16, 2015)

On-site Registration — JPY 50,000 JPY 20,000

Banquet Fee (On March 29, 2015) — JPY 10,000 JPY 10,000  
(at Port of Nagoya Public Aquarium)

\* Refunds cannot be made at any reason.

## Contact

**ISPlasma2015 / IC-PLANTS2015 Secretariat  
Y's Secretary Fields**

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